



NOTES

1. COATING (S1) : LOW GDD COATING  
 $R_s > 99\% @ 1400 \text{ nm} - 1700 \text{ nm}, A0l = 45^\circ$   
 $R_p > 99\% @ 1500 \text{ nm} - 1600 \text{ nm}, A0l = 45^\circ$
2. GDD:  
 $|GDD_s| < 30 \text{ fs}^2 @ 1400 \text{ nm} - 1700 \text{ nm}, A0l = 45^\circ$   
 $|GDD_p| < 30 \text{ fs}^2 @ 1500 \text{ nm} - 1600 \text{ nm}, A0l = 45^\circ$
3. CLEAR APERTURE (S1, S2) :  $> 90\% \text{ CA}$
4. SURFACE QUALITY (S1, S2) : 40/20(S/D)
5. SURFACE FLATNESS (S1) :  $\lambda / 10 @ 633 \text{ nm}$
6. PARALLELISM (S1, S2) :  $< 10 \text{ arcsec}$
7. CHAMFER: 0.1 mm,  $45^\circ$
8. THICKNESS TOLERANCE:  $\pm 0.1 \text{ mm}$
9. DIAMETER TOLERANCE:  $+0.0 \text{ mm} / -0.1 \text{ mm}$
10. OTHER SURFACES: FINE GROUND

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE	UFPM20-C			
DRAWN	LZHOU	Aug./5th/24	ULTRAFAST MIRROR $\text{Ø} 50.8 \text{ mm} \times 12 \text{ mm}, 1400 \text{ nm} - 1700 \text{ nm}$			
APPROVAL	WCHENG	Aug./5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	26.5 g	1:1	B